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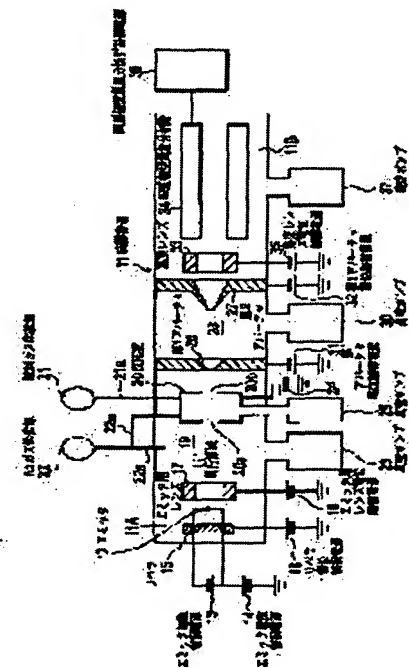
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## (54) MASS SPECTROMETRY AND MASS SPECTROGRAPH FOR HALOGENATED COMPOUND

(57)Abstract:

**PROBLEM TO BE SOLVED:** To provide a mass spectrometry and mass spectrograph for a halogenated compound capable of accurately measuring a fluorinated compound or the like affecting a large influence to a global warming issue by applying a Fujii's positive ion adhering method to the mass spectrometry of a halogenated compound.

**SOLUTION:** The mass spectrograph for halogenated compound comprises an emitter 12 for radiating metal ion, a reaction chamber 20 for introducing a gas to be detected and ionizing the gas by the metal ion, apertures 26, 27, etc., for guiding the molecules of the ionized gas to be detected, and a mass spectrometer 34 for measuring the introduced molecules. In this case, the metal ion radiated from the emitter is made to fly to the chamber and ionized therein. The gas to be detected is the halogenated compound. The mass spectrograph further comprises a sample gas supply source 21 for supplying the halogenated compound to the chamber, and an N<sub>2</sub> gas supply source 22 for supplying a gas (N<sub>2</sub> or the like) hardly adhering metal ion as compared with the halogenated compound to the chamber.



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